

This application is a continuation-in-part of U.S. Patent Application Ser. No. 09/350,210, filed July 9, 1999, now U.S. Pat. No. 6,267,853, a continuation-in-part of U.S. Patent Application Ser. No. 09/350,212, filed July 9, 1999, now U.S. Pat. No. 6,516,815, and a continuation-in-part of U.S. Patent Application Ser. No. 09/614,406, filed July 12, 2000, now U.S. Pat. No. 6,494,219.

IN THE CLAIMS:

Please amend the claims as follows:

1. (Amended) An integrated bevel cleaning (IBC) apparatus, comprising:
 - a transfer position where a substrate is positioned;
 - a rinse position where the substrate is rinsed;
 - an etch position where the edge of the substrate is cleaned;
 - an actuator for positioning the substrate in the transfer position, the rinse position and the etch position; and
 - a plurality of cooperatively movable etchant dispense nozzles configured to dispense an etchant onto the front side and backside of the substrate.
4. (Amended) The IBC apparatus of claim 1 further comprising at least one rinsing nozzle located proximate the rinsing position for rinsing at least an edge region of the substrate.
5. (Amended) The IBC apparatus of claim 4 wherein the at least one rinsing nozzle comprises a plurality of rinsing nozzles positioned to rinse the front side and backside of the substrate.

BEST AVAILABLE COPY